

POLOS® PM-100

The POLOS® PM-100 is capable of writing structures up to $0.3\ \mu\text{m}$. It is a versatile UV laser writer with ultra-high precision components, specifically designed to give the user the highest degree of freedom to create micro-structures in photosensitive layers.



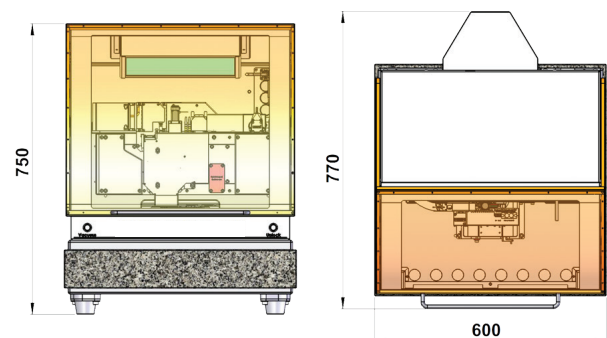
The POLOS® PM-100 system includes a 405 nm optical module capable of writing structures as small as $0.3\ \mu\text{m}$. This user-friendly tool supports up to 4095 levels of gray-scale or pure binary mode and allows for 3D optical structures, surface structures as well as mask projects. Real time laser controlled auto-focus and laser intensity control ensure high quality imaging during the entire exposure process. The control electronics are all mounted within the frame except for the control PC. This Microsoft Windows based desktop PC and all required software is included in the package.

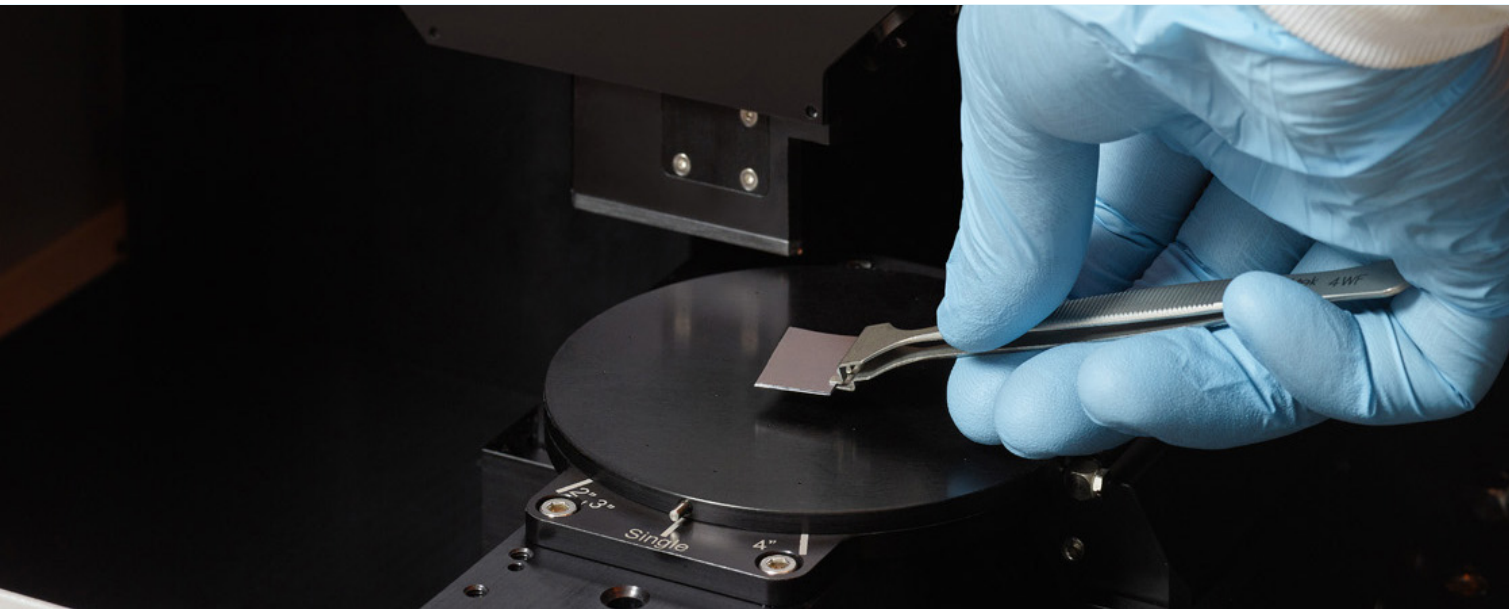
CONFIGURATION

| | |
|---------------------|---|
| Max. writeable size | 4 x 4" |
| Stroke scan & step | Max. 115 mm |
| Repeatability | < 50 nm RMS |
| Encoder resolution | 2.5 nm |
| Scan speed | Max. 200 mm/s |
| Straightness axis | < $1\ \mu\text{m}$ over 100 mm |
| Wafer thickness | 0 - 10 mm |
| Max. substrate size | Min. 5 x 5 mm, max. 125 x 125 mm |
| Exposable area | Max. 110 x 110 mm (speed dependent) |
| Dimensions (mm) | 600 (w) x 750 (h) x 600 mm (d) (excluding optional air duct) |
| Weight (kg) | 260 |
| Compressed air: | 5 - 7 Bar, Air quality according ISO8573-1:2010 class 3 or better |

KEY BENEFITS

- Writing resolution down to $0.3\ \mu\text{m}$ (Highest resolution on the market with 405 nm laser)
- 375 nm laser source available for more demanding applications
- Minimal maintenance costs
- Compact optical module: use a spare optical unit for revolutionary machine downtime reduction
- User-friendly operation





| OPTICAL PROPERTIES | |
|--------------------|---|
| Laser source | Standard 405 nm, GaN laser diode. 375 nm optional |
| Lifetime | >10.000 hours |
| Write modes | 0.3 μm , optional 0.6 μm and 0.9 μm FWHM |
| NA | 0.85 |
| Working distance | 0.6 mm |
| Intensity | Max. 3 mW in the spot. Software controllable |
| Grayscale control | 4095 levels |
| Autofocus | 800 Hz bandwidth, 650 nm red laser controlled +/- 0.3 mm height variation with auto height tracking Fast voice coil actuator for accurate real time Z correction |
| Focus offset | Adjustable by software control |